

MOS FIELD-EFFECT TRANSISTORS (MOSFET)

- $\left. \begin{matrix} n \\ p \end{matrix} \right\} \text{ MOSFET } \left\{ \begin{matrix} \text{DEPLETION-MODE} \\ \text{ENHANCEMENT-MODE} \end{matrix} \right.$

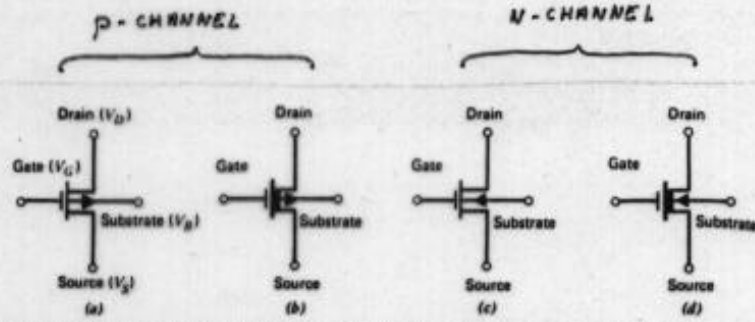


Figure 9.2 Electrical symbols for MOSFETs: (a) p-channel enhancement, (b) p-channel depletion, (c) n-channel enhancement, (d) n-channel depletion devices.

→ p-n junction between substrate and channel

n- MOSFET: ENHANCEMENT MODE

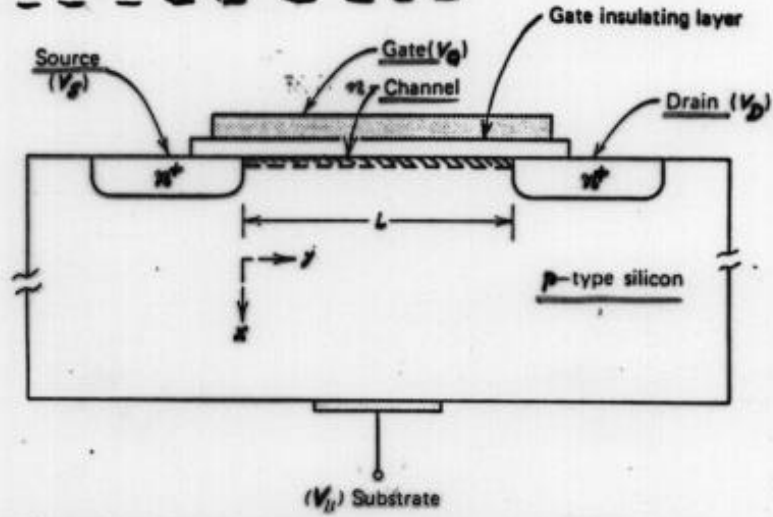
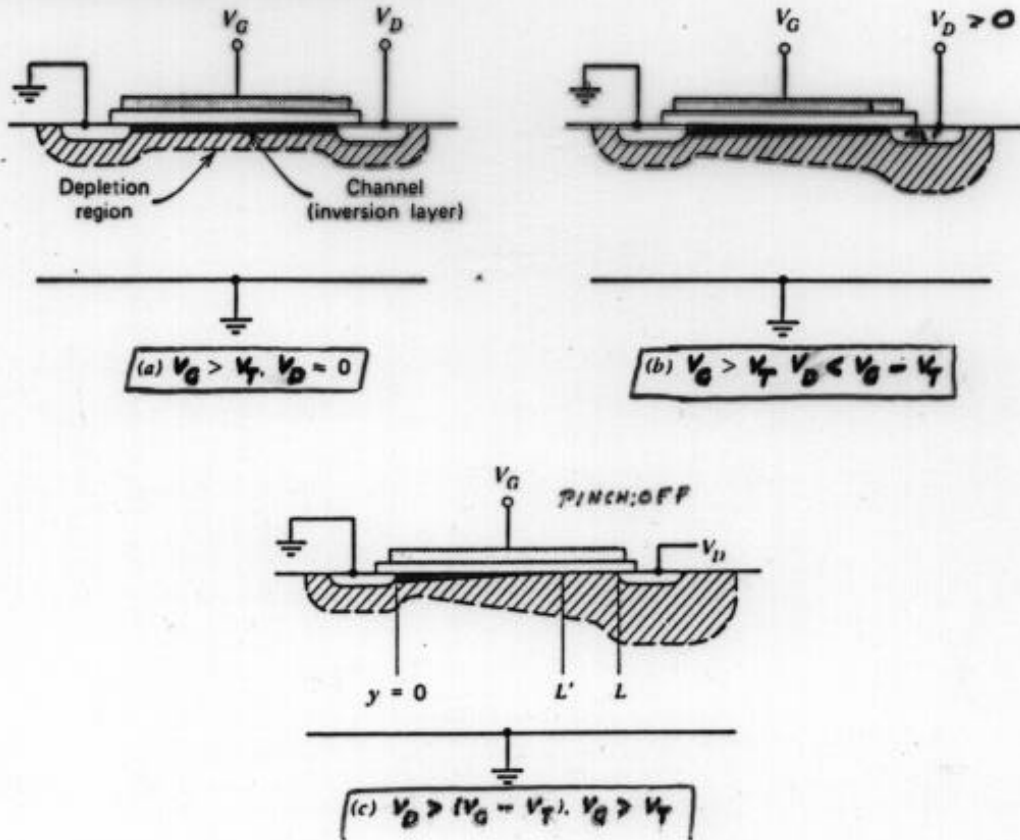
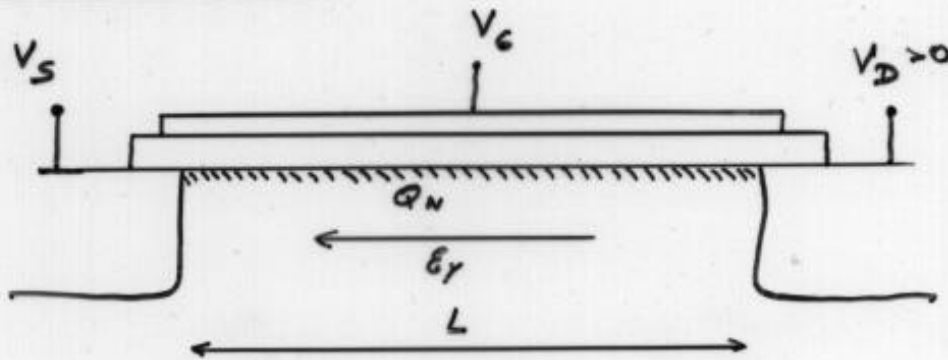


Figure 9.1 Basic elements of an n-channel, MOSFET. The source to drain spacing is designated L and the device width (in the z direction) is W .

CHARGE CONTROL OPERATION



LUMPED ANALYSIS



$$\boxed{I_D = - \frac{Q_N}{T_{tr}}}$$

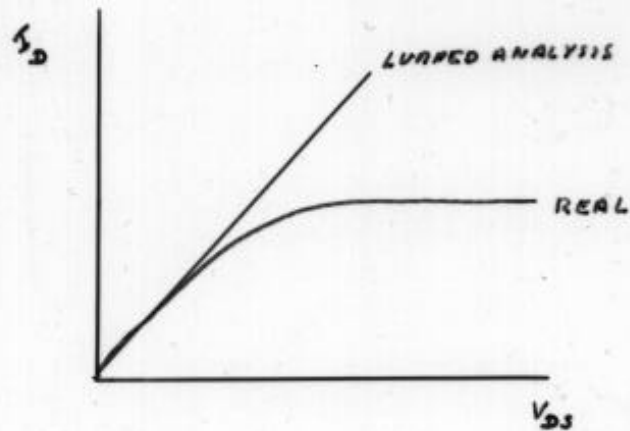
Q_N : CHANNEL CHARGE = $Q_m WL$
CHARGE DENSITY
CHANNEL WIDTH
 $= - C_{ox} (V_G - V_T) WL$

$$\boxed{T_{tr} = \frac{L}{v_d}}$$

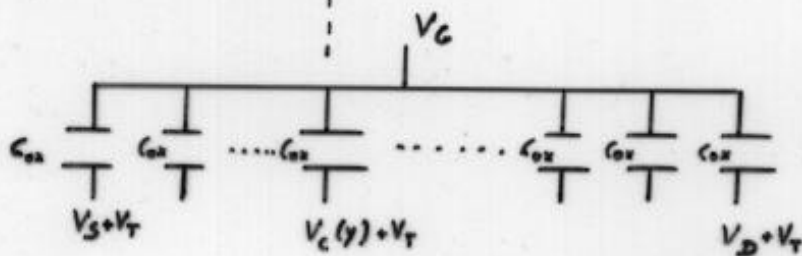
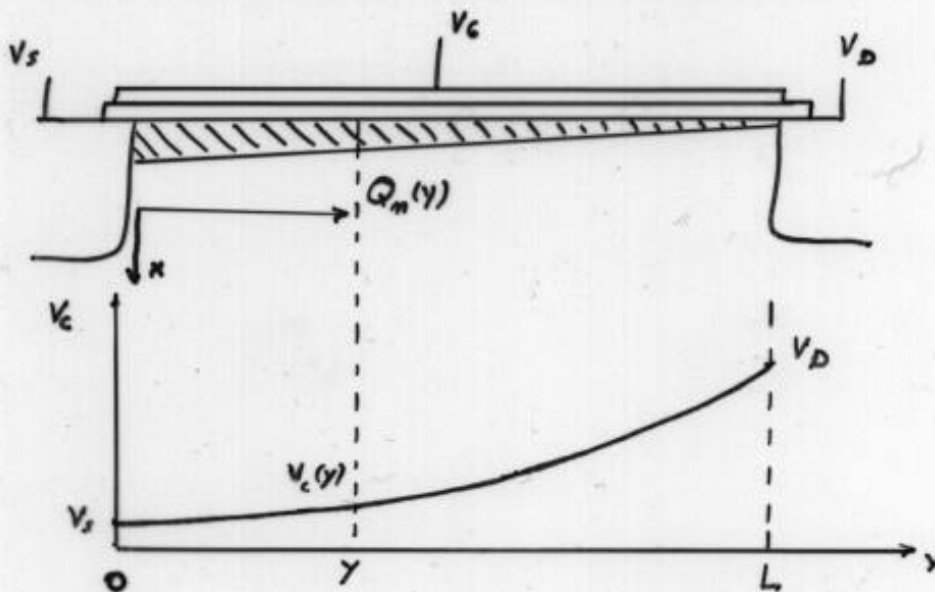
$$\begin{cases} v_d = -\mu_n E_Y \\ |E_Y| = \frac{V_D - V_S}{L} \end{cases}$$

$$\Rightarrow I_D = \mu_n C_{ox} \frac{W}{L} (V_G - V_T) V_{DS}$$

$$\boxed{I_D \propto (V_G - V_T) / V_{DS}}$$



GRADUAL CHANNEL APPROXIMATION ($V_{GT} \gg V_D$)



WHAT IS $Q_m(y)$? \Rightarrow $Q_m(y) = -C_{ox} [V_G - V_T - V_c(y)]$

CONDITIONS: $V_{GT} \gg V_D$

OR $\begin{cases} |\frac{\partial \phi}{\partial y}| \ll |\frac{\partial \phi}{\partial x}| \\ |\mathcal{E}_y| \ll |\mathcal{E}_x| \end{cases}$

ϕ : ELECTROSTATIC POTENTIAL